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SERIAL NUMBER REQUEST DATE		FIRST NAMED APPLICANT	ATTORNEY DOCKET NO.
10/552	606 3/24/06	TOMOHARU NAKANO, ET AL.	052463
Title:	POLISHING LIQUID FOR POLISHING METHOD	CMP PROCESS AND	
Correspond	ence Address:		Art Unit Paper Number
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LICENSE FOR FOREIGN FILING

[Title 35, United States Code (1952) Sections 184, 185, 186]



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Petitioner:

NAKANO, et al.

:DECISION ON REQUEST

:UNDER 37 CFR 5.25

Petition No.:

10/552,606

Petition Filing Date:

24 March 2006

Docket No.:

052463

Title: POLISHING LIQUID FOR CMP PROCESS AND POLISHING METHOD

This is a decision on the petition for retroactive foreign filing license.

It has been determined that a retroactive license for foreign filing under 35 U.S.C. 184 be granted with respect to the filing(s) listed below. The petition complies with 37 C.F.R. 5.25 in that there is an adequate showing that the subject matter in question was not under secrecy order, that the license was diligently sought, and that the material was filed abroad without the required license under 37 C.F.R 5.11 through error and without deceptive intent.

Foreign Filing Location	Date	
Japan	07 May 2004	
Taiwan	07 May 2004	
Malaysia	07 May 2004	
· / _	•	

Yvonne R. Abbott, Esq. Patent Examiner

Licensing & Review

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